

3.

2

~~8.~~ (Amended) A mask according to claim ~~7~~², wherein said bright pattern is regularly

arranged.

4.

~~9.~~ (Amended) A mask according to claim ~~7~~², wherein said bright pattern is irregularly

arranged.

8.

~~11.~~ (Amended) A mask according to claim ~~10~~⁷, wherein the maximum value of said pitch

is determined so that a concave and convex pattern formed by transferring said dark pattern on said mask onto a substrate is not more than resolution of an alignment sensor.

9.

~~12.~~ (Amended) A mask according to claim ~~10~~⁷, wherein said dark pattern is regularly

arranged.

10.

~~13.~~ (Amended) A mask according to claim ~~10~~⁷, wherein said dark pattern is irregularly

arranged.

13.

~~24.~~ (Amended) An exposure apparatus comprising:

a projection optical system which projects an image of a mark on a mask onto a substrate to form an alignment mark on said substrate; and

an alignment sensor which detects said alignment mark formed on said substrate,

wherein said alignment mark includes a plurality of first patterns having a height and a second pattern for preventing a file covering the alignment mark from being depressed.